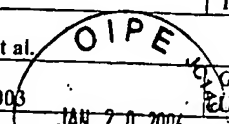


<b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)	Docket Number (Optional) TWI-33110	Application Number 10/714,460
	Applicant(s) Rodney Smedt et al.	
	Filing Date November 14, 2003	Group Art Unit Unknown
		

### U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE
12	*AA	4,200,395	04/29/1980	Smith et al.	356	356	05/03/1977
12	*AB	4,757,207	07/12/1988	Chappelow et al.	250	491.1	03/03/1987
12	*AC	5,216,257	06/01/1993	Brueck et al.	250	548	07/09/1990
12	*AD	5,343,292	08/30/1994	Brueck et al.	356	363	10/19/1990
12	*AE	5,805,290	09/08/1998	Ausschnitt et al.	356	401	05/02/1996
12	*AF	6,023,338	02/08/2000	Bareket	356	401	07/12/1996
12	*AG	6,079,256	06/27/2000	Bareket	73	105	12/07/1998
12	*AH	6,462,818	10/08/2002	Bareket	356	401	06/22/2000
12	*AI	6,483,580	11/19/2002	Xu et al.	356	300	03/06/1998
12	*AJ	US 2002/0158193	10/31/2002	Sezginer et al.	250	237	02/12/2002
12	*AK	US 2002/0192577	12/19/2002	Fay et al.	430	22	06/15/2001
12	*AL	US 2003/0002043	01/02/2003	Abdulhalim et al.	356	400	04/10/2001
12	*AM	US 2003/0043372	03/06/2003	Schulz	356	327	04/29/2002
12	*AN	US 2003/0042579	03/06/2003	Schulz	257	629	04/29/2002
12	*AO	US 2003/0044702	03/06/2003	Schulz	430	30	04/29/2002
12	*AP	US 2003/0190793	10/09/2003	Brill et al.	438	401	09/20/2001

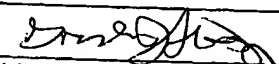
### FOREIGN PATENT DOCUMENTS

REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
12	AQ	WO 02/25723 A2	03/28/2002	PCT	H01L	21/66	

### OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

12	AR	H-T. Huang et al., "Scatterometry-Based Overlay Metrology," <i>Metrology, Inspection, and Process Control for Microlithography XVII, Proceedings of SPIE</i> , Vol. 5038 (2003), pp. 126-137.
12	AS	P. Heimann, "The Color-Box alignment vernier: a sensitive lithographic alignment vernier read at low magnification," <i>Optical Engineering</i> , Vol. 29, No. 7, July 1990, pp. 828-836.
12	AT	K.M. Monahan, "Handbook of Critical Dimension Metrology and Process Control," <i>Critical Reviews of Optical Science and Technology, SPIE</i> , Vol. CR52, proceedings of a conference held 28-29 September 1993, pp. cover, 160-188.

Examiner 	Date Considered 3/15/06
Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	